This listing of claims will replace all prior versions, and listings, of claims in the application:

Listing of Claims

- 1. (Cancelled).
- 2. (Currently Amended) The plastic substrate for organic electroluminescent devices as claimed in claim [[1]] 6, wherein the predetermined thickness is 0.1 to 4.5μm.
 - 3. (Cancelled).
- (Currently Amended) The fabrication method for the plastic substrate for organic electroluminescent devices as claimed in claim [[3]] 8, wherein the predetermined thickness is 0.1 to 4.5μm.
 - (Currently Amended) An organic electroluminescent device, comprising:
 a cathode;

an anode;

at least an organic layer between the anode and the cathode, such that when a voltage is applied to the cathode and the anode, the organic layer electroluminesces;

a first plastie substrate beneath the cathode; and

a plastic substrate; and

a deposition film with a predetermined thickness formed on the plastic substrate by plasma chemical vapor deposition, the film having a formula of $SiO_eC_aH_bX_cY_dZ_f$, wherein both $e \le 2$ and 2-e = a + b + c + d + f are satisfied, wherein X, Y and Z are selected from the group consisting of Sc, Ti, V, Cr, Mn, Fe, Co, Ni, Cu, Zn, Pd, Ag, Pt, Au and the elements in periodic table IA, IIA, IIIA, IVA, VA, VIA and VIIA excepting H, the deposition film having transparency of at least 97%.

6. (Currently Amended) The A plastic substrate for organic electroluminescent devices as elaimed in claim 1, further comprising:

a plastic substrate;

a deposition film with a predetermined thickness formed on the plastic substrate by plasma chemical vapor deposition, the film having a formula of SiO_cC_aH_bX_cY_dZ_f, wherein both e \leq 2 and 2-e = a + b + c + d + f are satisfied, wherein X, Y and Z are selected from the group consisting of Sc, Ti, V, Cr, Mn, Fe, Co, Ni, Cu, Zn, Pd, Ag, Pt, Au and the elements in periodic table IA, IIA, IIIA, IVA, VA, VIA and VIIA excepting H, the deposition film having transparency of at least 97%; and

a plurality of interface covalent bonds disposed between the deposition film layer and the plastic substrate.

7. (Previously Presented) The plastic substrate for organic electroluminescent devices as claimed in claim 6, wherein a thickness of the interface covalent bonds is 20 to 30Å.

8. (Currently Amended) The A fabrication method for the plastic substrate for organic electroluminescent devices as elaimed in claim 3, comprising the steps of:

providing a plastic substrate; and

performing plasma chemical vapor deposition to form a deposition film of predetermined thickness on the plastic substrate, the film having a formula of $SiO_eC_aH_bX_eY_dZ_f$, wherein both $e \le 1$ 2 and 2-e = a + b + c + d + f are satisfied, wherein X, Y and Z are selected from the group consisting of Sc. Ti, V, Cr, Mn, Fe, Co, Ni, Cu, Zn, Pd, Ag, Pt, Au and the elements in periodic table IA, IIA, IIIA, IVA, VA, VIA and VIIA excepting H, the deposition film having transparency of at least 97%, wherein a plurality of free radicals in the plasma produce an interface covalent bonds between the deposition film layer and the plastic substrate.

- 9. (Previously Presented) The fabrication method for the plastic substrate for organic electroluminescent devices as claimed in claim 8, wherein a thickness of the interface covalent bonds is 20 to 30Å.
 - 10. (Currently Amended) An organic electroluminescent device, comprising:
 - a first electrode;
 - a second electrode;
- at least an electroluminescent layer between the first electrode and the second electrode, such that when a voltage is applied to the first electrode and the second electrode, the electroluminescent layer electroluminesces;
 - a first plastie substrate beneath the first electrode; and

a second plastic substrate as claimed in claim-1 above the second electrode, comprising:

a plastic substrate; and

a deposition film with a predetermined thickness formed on the plastic substrate by plasma chemical vapor deposition, the film having a formula of $SiO_eC_aH_bX_cY_dZ_f$, wherein both $e \le 2$ and 2-e = a + b + c + d + f are satisfied, wherein X, Y and Z are selected from the group consisting of Sc, Ti, V, Cr, Mn, Fe, Co, Ni, Cu, Zn, Pd, Ag, Pt, Au and the elements in periodic table IA, IIA, IIIA, IVA, VA, VIA and VIIA excepting H, the deposition film having transparency of at least 97%.

- 11. (Cancelled)
- 12. (Currently Amended) The plastic substrate for organic electroluminescent devices as claimed in claim [[11]] 16, wherein the predetermined thickness is 0.1 to 4.5μm.
 - 13. (Cancelled)
- 14. (Currently Amended) The fabrication method for the plastic substrate for organic electroluminescent devices as claimed in claim [[13]] 18, wherein the predetermined thickness is 0.1 to 4.5μm.
 - 15. (Currently Amended) An organic electroluminescent device, comprising: a cathode;
 an anode;

at least an organic layer between the anode and the cathode, such that when a voltage is applied to the cathode and the anode, the organic layer electroluminesces;

a first plastic substrate beneath the cathode; and

a second plastic substrate as claimed in claim 11 above the anode, comprising:

a plastic substrate; and

a deposition film with a predetermined thickness formed on the plastic substrate by plasma chemical vapor deposition, the film having a formula of SiO_eC_aH_bX_cY_dZ_f wherein both e < 2 and 2 - e = a + b + c + d + f are satisfied, wherein X, Y and Z are selected from the group consisting of Sc, Ti, V, Cr, Mn, Fe, Co, Ni, Cu, Zn, Pd, Ag, Pt, Au and the elements in periodic table IA, IIA, IIIA, IVA, VA, VIA and VIIA excepting H.

16. (Currently Amended) The A plastic substrate for organic electroluminescent devices as claimed in claim 11, further comprising:

a plastic substrate;

a deposition film with a predetermined thickness formed on the plastic substrate by plasma chemical vapor deposition, the film having a formula of SiO_eC_aH_bX_cY_dZ_f wherein both e \leq 2 and 2-e = a + b + c + d + f are satisfied, wherein X, Y and Z are selected from the group consisting of Sc, Ti, V, Cr, Mn, Fe, Co, Ni, Cu, Zn, Pd, Ag, Pt, Au and the elements in periodic table IA, IIA, IIIA, IVA, VA, VIA and VIIA excepting H; and

a plurality of interface covalent bonds disposed between the deposition film layer and the plastic substrate.

- 17. (Previously Presented) The plastic substrate for organic electroluminescent devices as claimed in claim 16, wherein a thickness of the interface covalent bonds is 20 to 30Å.
- 18. (Currently Amended) The A fabrication method for the plastic substrate for organic electroluminescent devices as claimed in claim 13, comprising the steps of:

providing a plastic substrate; and

performing plasma chemical vapor deposition to form a deposition film of predetermined thickness on the plastic substrate, the film having a formula of $SiO_eC_aH_bX_cY_dZ_f$ wherein both $e \le 1$ 2 and 2-e = a + b + c + d + f are satisfied, wherein X, Y and Z are selected from the group consisting of Sc, Ti, V, Cr, Mn, Fe, Co, Ni, Cu, Zn, Pd, Ag, Pt, Au and the elements in periodic table IA, IIA, IIIA, IVA, VA, VIA and VIIA excepting H, wherein a plurality of free radicals in the plasma produce a plurality of interface covalent bonds between the deposition film layer and the plastic substrate.

- 19. (Previously Presented) The fabrication method for the plastic substrate for organic electroluminescent devices as claimed in claim 18, wherein a thickness of the interface covalent bonds is 20 to 30Å.
 - 20. (Currently Amended) An organic electroluminescent device, comprising: a first electrode; a second electrode;

- a first plastie substrate beneath the first electrode; and
- a second plastic substrate as claimed in claim 11 above the second electrode, comprising:

 a plastic substrate; and

a deposition film with a predetermined thickness formed on the plastic substrate by plasma chemical vapor deposition, the film having a formula of $SiO_eC_aH_bX_cY_dZ_f$, wherein both e < 2 and 2 - e = a + b + c + d + f are satisfied, wherein X, Y and Z are selected from the group consisting of Sc, Ti, V, Cr, Mn, Fe, Co, Ni, Cu, Zn, Pd, Ag, Pt, Au and the elements in periodic table IA, IIA, IIIA, IVA, VA, VIA and VIIA excepting H.